

<b><u>Claim 28</u></b>	<b><u>Description in Specification of Application</u></b> <b><u>No. 09/139,296</u></b>
28. A lithographic device comprising the following elements which are supported in that order:	Fig. 1; page 1, lines 6-12, page 2, line 20 - page 3, line 2, page 20, lines 18-23
a substrate stage which can be positioned by a first positioning device parallel to a Y-direction which is perpendicular to a vertical Z-direction and an X-direction which is perpendicular to the Y-direction and to the Z-direction;	Fig. 1; items 19-22, 25-27; page 16, line 21 - page 17, line 1
an imaging system with a main axis directed parallel to the Z-direction;	Fig. 1; item 14; page 15, line 21 - page 16, line 5
a mask stage which can be positioned parallel to the Y-direction by a second positioning device; and	Figs. 1 and 5-7; items 8, 9, 31A, 31B, 39A, 39B, 42A, 42B are parts of a mask stage; page 1, line 18, page 2, lines 23-24, page 3, lines 5-17, page 21, lines 1-5, page 21, lines 13-16
an illumination optical system which irradiates an exposure illumination light beam;	Fig. 1; items 1-5; page 15, lines 5-20, page 21, lines 19-23
wherein the mask stage is also positionable parallel to the X-direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device; and	Page 3, lines 5-17, page 21, lines 13-16, page 25, lines 8-21
wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the Y-direction and X-direction and can be rotated about the axis of rotation of the mask stage and a second linear motor by means of which the mask stage can be positioned over comparatively great movement parallel to the Y-direction.	Items 39A, 39B, 42A, 42B are parts of first linear motor;  Items 31A, 31B are parts of second linear motor;  Page 21, lines 1-5, page 21, lines 13-16, page 21, line 23 - page 22, line 2

<b><u>Claim 29</u></b>	<b><u>Description in Specification of Application</u></b> <b><u>No. 09/139,296</u></b>
29. A lithographic device comprising the following elements which are supported in that order:	Fig. 1; page 1, lines 6-12, page 2, line 20 - page 3, line 2, page 20, lines 18-23
a substrate stage which can be positioned by a first positioning device parallel to a Y-direction which is perpendicular to a vertical Z-direction and an X-direction which is perpendicular to the Y-direction and to the Z-direction;	Fig. 1; items 19-22, 25-27; page 16, line 21 - page 17, line 1
an imaging system with a main axis directed parallel to the Z-direction;	Fig. 1; item 14; page 15, line 21 - page 16, line 5
a mask stage which can be positioned parallel to the Y-direction by a second positioning device; and	Figs. 1 and 5-7; items 8, 9, 31A, 31B, 39A, 39B, 42A, 42B are parts of a mask stage; page 1, line 18, page 2, lines 23-24, page 3, lines 5-17, page 21, lines 1-5, page 21, lines 13-16
an illumination optical system which irradiates an exposure illumination light beam;	Fig. 1; items 1-5; page 15, lines 5-20, page 21, lines 19-23
wherein the mask stage is also positionable parallel to the X-direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device;	Page 3, lines 5-17, page 21, lines 13-16, page 25, lines 8-21
wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the Y-direction and X-direction and can be rotated about the axis of rotation of the mask stage and a second linear motor by means of which the mask stage can be positioned over comparatively great movement parallel to the Y-direction; and	Items 39A, 39B, 42A, 42B are parts of first linear motor;  Items 31A, 31B are parts of second linear motor;  Page 21, lines 1-5, page 21, lines 13-16, page 21, line 23 - page 22, line 2

<b><u>Claim 29</u></b>	<b><u>Description in Specification of Application</u></b> <b><u>No. 09/139,296</u></b>
wherein a magnet system and an electric coil system belong to the first linear motor, while the second linear motor comprises a stationary part and a movable part which is displaceable parallel to the Y-direction over a guide of the stationary part, the magnet system of the first linear motor being fastened to the mask stage and the electric coil system of the first linear motor being fastened to the movable part of the second linear motor.	<p>Items 37A, 37B, 40A, 40B are magnets of first linear motor, and are fixed to fine adjustment stage 8;</p> <p>Items 38A, 38B, 41A, 41B are coils of first linear motor, and are fixed to scanning stage 9 to which movable parts 32A, 32B of second linear motor 31A, 31B are fixed;</p> <p>Second linear motor 31A, 31B has movable parts 32A, 32B and stationary parts 33A, 33B;</p> <p>Page 18, lines 11-21, page 21, lines 3-5, page 23, lines 10-20, page 23, line 26 - page 24, line 2, page 24, lines 3-9, page 24, line 13 - page 25, line 2, page 28, lines 4-13</p>

<b><u>Claim 30</u></b>	<b><u>Description in Specification of Application</u></b> <b><u>No. 09/139,296</u></b>
30. A lithographic device comprising the following elements which are supported in that order:	Fig. 1; page 1, lines 6-12, page 2, line 20 - page 3, line 2, page 20, lines 18-23
a substrate stage which can be positioned by a first positioning device parallel to a first direction which is perpendicular to a vertical Z-direction and a second direction which is perpendicular to the first direction and to the Z-direction;	Fig. 1; items 19-22, 25-27; page 16, line 21 - page 17, line 1
an imaging system with a main axis directed parallel to the Z-direction;	Fig. 1; item 14; page 15, line 21 - page 16, line 5
a mask stage which can be positioned parallel to the first direction by a second positioning device; and	Figs. 1 and 5-7; items 8, 9, 31A, 31B, 39A, 39B, 42A, 42B are parts of a mask stage; page 1, line 18, page 2, lines 23-24, page 3, lines 5-17, page 21, lines 1-5, page 21, lines 13-16
an illumination optical system which irradiates an exposure illumination light beam;	Fig. 1; items 1-5; page 15, lines 5-20, page 21, lines 19-23

<b><u>Claim 30</u></b>	<b><u>Description in Specification of Application</u></b> <b><u>No. 09/139,296</u></b>
wherein the mask stage is also positionable parallel to the second direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device; and	Page 3, lines 5-17, page 21, lines 13-16, page 25, lines 8-21
wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the first direction and the second direction and can be rotated about the axis of rotation of the mask stage and a second linear motor by means of which the mask stage can be positioned over comparatively great movement parallel to the first direction.	Items 39A, 39B, 42A, 42B are parts of first linear motor;  Items 31A, 31B are parts of second linear motor;  Page 21, lines 1-5, page 21, lines 13-16, page 21, line 23 - page 22, line 2

<b><u>Claim 31</u></b>	<b><u>Description in Specification of Application</u></b> <b><u>No. 09/139,296</u></b>
31. A lithographic device comprising the following elements which are supported in that order:	Fig. 1; page 1, lines 6-12, page 2, line 20 - page 3, line 2, page 20, lines 18-23
a substrate stage which can be positioned by a first positioning device parallel to a first direction which is perpendicular to a vertical Z-direction and a second direction which is perpendicular to the first direction and to the Z-direction;	Fig. 1; items 19-22, 25-27; page 16, line 21 - page 17, line 1
an imaging system with a main axis directed parallel to the Z-direction;	Fig. 1; item 14; page 15, line 21 - page 16, line 5
a mask stage which can be positioned parallel to the first direction by a second positioning device; and	Figs. 1 and 5-7; items 8, 9, 31A, 31B, 39A, 39B, 42A, 42B are parts of a mask stage; page 1, line 18, page 2, lines 23-24, page 3, lines 5-17, page 21, lines 1-5, page 21, lines 13-16
an illumination optical system which irradiates an exposure illumination light beam;	Fig. 1; items 1-5; page 15, lines 5-20, page 21, lines 19-23

<b><u>Claim 31</u></b>	<b><u>Description in Specification of Application</u></b> <b><u>No. 09/139,296</u></b>
wherein the mask stage is also positionable parallel to the second direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device;	Page 3, lines 5-17, page 21, lines 13-16, page 25, lines 8-21
wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the first direction and the second direction and can be rotated about the axis of rotation of the mask stage and a second linear motor by means of which the mask stage can be positioned over comparatively great movement parallel to the first direction; and	Items 39A, 39B, 42A, 42B are parts of first linear motor;  Items 31A, 31B are parts of second linear motor;  Page 21, lines 1-5, page 21, lines 13-16, page 21, line 23 - page 22, line 2
wherein a magnet system and an electric coil system belong to the first linear motor, while the second linear motor comprises a stationary part and a movable part which is displaceable parallel to the first direction over a guide of the stationary part, the magnet system of the first linear motor being fastened to the mask stage and the electric coil system of the first linear motor being fastened to the movable part of the second linear motor.	Items 37A, 37B, 40A, 40B are magnets of first linear motor, and are fixed to fine adjustment stage 8;  Items 38A, 38B, 41A, 41B are coils of first linear motor, and are fixed to scanning stage 9 to which movable parts 32A, 32B of second linear motor 31A, 31B are fixed;  Second linear motor 31A, 31B has movable parts 32A, 32B and stationary parts 33A, 33B;  Page 18, lines 11-21, page 21, lines 3-5, page 23, lines 10-20, page 23, line 26 - page 24, line 2, page 24, lines 3-9, page 24, line 13 - page 25, line 2, page 28, lines 4-13

<b><u>Claim 32</u></b>	<b><u>Description in Specification of Application</u></b> <b><u>No. 09/139,296</u></b>
32. A lithographic device comprising the following elements which are arranged in that order:	Fig. 1; page 1, lines 6-12, page 2, line 20 - page 3, line 2, page 20, lines 18-23
a substrate stage which can be positioned by a first positioning device parallel to a first direction which is perpendicular to a vertical Z-direction and a second direction which is perpendicular to the first direction and to the Z-direction;	Fig. 1; items 19-22, 25-27; page 16, line 21 - page 17, line 1

<b><u>Claim 32</u></b>	<b><u>Description in Specification of Application</u></b> <b><u>No. 09/139,296</u></b>
an imaging system with a main axis directed parallel to the Z-direction;	Fig. 1; item 14; page 15, line 21 - page 16, line 5
a mask stage which can be positioned parallel to the first direction by a second positioning device; and	Figs. 1 and 5-7; items 8, 9, 31A, 31B, 39A, 39B, 42A, 42B are parts of a mask stage; page 1, line 18, page 2, lines 23-24, page 3, lines 5-17, page 21, lines 1-5, page 21, lines 13-16
an illumination optical system which irradiates an exposure illumination light beam;	Fig. 1; items 1-5; page 15, lines 5-20, page 21, lines 19-23
wherein the mask stage is also positionable parallel to the second direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device; and	Page 3, lines 5-17, page 21, lines 13-16, page 25, lines 8-21
wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the first direction and the second direction and can be rotated about the axis of rotation of the mask stage and a second linear motor by means of which the mask stage can be positioned over comparatively great movement parallel to the first direction.	Items 39A, 39B, 42A, 42B are parts of first linear motor;  Items 31A, 31B are parts of second linear motor;  Page 21, lines 1-5, page 21, lines 13-16, page 21, line 23 - page 22, line 2

<b><u>Claim 33</u></b>	<b><u>Description in Specification of Application</u></b> <b><u>No. 09/139,296</u></b>
33. A lithographic device comprising the following elements which are arranged in that order:	Fig. 1; page 1, lines 6-12, page 2, line 20 - page 3, line 2, page 20, lines 18-23
a substrate stage which can be positioned by a first positioning device parallel to a first direction which is perpendicular to a vertical Z-direction and a second direction which is perpendicular to the first direction and to the Z-direction;	Fig. 1; items 19-22, 25-27; page 16, line 21 - page 17, line 1
an imaging system with a main axis directed parallel to the Z-direction;	Fig. 1; item 14; page 15, line 21 - page 16, line 5

<b><u>Claim 33</u></b>	<b><u>Description in Specification of Application No. 09/139,296</u></b>
a mask stage which can be positioned parallel to the first direction by a second positioning device; and	Figs. 1 and 5-7; items 8, 9, 31A, 31B, 39A, 39B, 42A, 42B are parts of a mask stage; page 1, line 18, page 2, lines 23-24, page 3, lines 5-17, page 21, lines 1-5, page 21, lines 13-16
an illumination optical system which irradiates an exposure illumination light beam;	Fig. 1; items 1-5; page 15, lines 5-20, page 21, lines 19-23
wherein the mask stage is also positionable parallel to the second direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device;	Page 3, lines 5-17, page 21, lines 13-16, page 25, lines 8-21
wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the first direction and the second direction and can be rotated about the axis of rotation of the mask stage and a second linear motor by means of which the mask stage can be positioned over comparatively great movement parallel to the first direction; and	<p>Items 39A, 39B, 42A, 42B are parts of first linear motor;</p> <p>Items 31A, 31B are parts of second linear motor;</p> <p>Page 21, lines 1-5, page 21, lines 13-16, page 21, line 23 - page 22, line 2</p>
wherein a magnet system and an electric coil system belong to the first linear motor, while the second linear motor comprises a stationary part and a movable part which is displaceable parallel to the first direction over a guide of the stationary part, the magnet system of the first linear motor being connected to the mask stage and the electric coil system of the first linear motor being connected to the movable part of the second linear motor so as to move with the movable part of the second linear motor.	<p>Items 37A, 37B, 40A, 40B are magnets of first linear motor, and are fixed to fine adjustment stage 8;</p> <p>Items 38A, 38B, 41A, 41B are coils of first linear motor, and are fixed to scanning stage 9 to which movable parts 32A, 32B of second linear motor 31A, 31B are fixed;</p> <p>Second linear motor 31A, 31B has movable parts 32A, 32B and stationary parts 33A, 33B;</p> <p>Page 18, lines 11-21, page 21, lines 3-5, page 23, lines 10-20, page 23, line 26 - page 24, line 2, page 24, lines 3-9, page 24, line 13 - page 25, line 2, page 28, lines 4-13</p>

In view of the foregoing and the March 17, 2003 Amendment, Applicant respectfully submits that claims 28-33 are allowable, and that an interference with U.S. Patent No. 5,767,948 should be declared.

Should the Examiner believe anything further would be desirable to place this application in even better condition for allowance, the Examiner is invited to contact Applicant's undersigned attorney at the telephone number set forth below.

Respectfully submitted,



Mario A. Costantino  
Registration No. 33,565

MAC/ccs

Date: June 23, 2003

**OLIFF & BERRIDGE, PLC**  
**P.O. Box 19928**  
**Alexandria, Virginia 22320**  
**Telephone: (703) 836-6400**

**DEPOSIT ACCOUNT USE  
AUTHORIZATION**

Please grant any extension  
necessary for entry;  
Charge any fee due to our  
Deposit Account No. 15-0461